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## » Key

IEEE JNL IEEE Journal or Magazine

IEEE JNL IEEE Journal or Magazine

IEEE CNF IEEE Conference Proceeding

IEEE CNF IEEE Conference Proceeding

IEEE STD IEEE Standard

- ☐ 1. **Plasma-induced charging damage to MOS capacitor structure in cyclotron-resonance plasmas**  
Friedmann, J.B.; Ma, S.-M.; McVittie, J.P.; Shohet, J.L.; Plasma Science, 1995. IEEE Conference Record - Abstracts., 1995. International Conference on 5-8 June 1995 Page(s):164  
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- ☐ 2. **Prediction of plasma charging induced gate oxide damage by probe**  
Shawming Ma; McVittie, J.P.; Saraswat, K.C.; [Electron Device Letters, IEEE](#)  
Volume 18, Issue 10, Oct. 1997 Page(s):468 - 470  
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- ☐ 3. **Evaluation of charge build-up in wafer processing by using with charge collecting electrodes**  
Kubo, H.; Namura, T.; Yoneda, K.; Ohishi, H.; Todokoro, Y.; [Microelectronic Test Structures, 1995. ICMTS 1995. Proceeding: International Conference on](#)  
22-25 March 1995 Page(s):5 - 9  
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- ☐ 4. **Resist-related damage on ultrathin gate oxide during plasma**  
Chao-Hsin Chien; Chun-Yen Chang; Horng-Chih Lin; Tsai-Fu Ch Chiou; Liang-Po Chen; Tiao-Yuan Huang;  
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- ☐ **5. Reduction and non-uniformity of high density plasma process: electrical degradation in MOS devices**  
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- ☐ **6. The role of resist for ultrathin gate oxide degradation during**  
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- ☐ **7. Sensitivity and limitations of plasma charging damage measurement on MOS capacitors structures**  
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- ☐ **8. A study of wafer charging with CHARM-2 and large area capacitance**  
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